



5/4
11/21/02

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of : **Confirmati n N . 4175**
Hideo HADA et al. : Docket No. 2001_1787A
Serial No. 09/996,676 : Group Art Unit 1752
Filed November 30, 2001 : Examiner R. Ashton

POSITIVE-WORKING
PHOTORESIST COMPOSITION

RECEIVED
NOV 21 2002
TC 1700

RESPONSE

Assistant Commissioner for Patents,
Washington, D.C.

THE COMMISSIONER IS AUTHORIZED
TO CHARGE ANY DEFICIENCY IN THE
FEES FOR THIS PAPER TO DEPOSIT
ACCOUNT NO. 23-0975

Sir:

In response to the Official Action dated July 18, 2002, the period of response having been extended for one month by the attached petition, please amend the present application as follows:

IN THE CLAIMS:

Please cancel claims 1-11 without prejudice to the subject matter thereof.

Please add new claims 12-17 as follows:

back of spec.

12. (New) A positive-working photoresist composition which comprises, as a uniform solution in an organic solvent:

- (A) 100 parts by weight of a resinous compound capable of being imparted with increased solubility in an aqueous alkaline solution by interaction with an acid;
- (B) from 0.5 to 30 parts by weight of a radiation-sensitive acid generating compound capable of generating an acid by irradiation with a radiation; and
- (C) an organic solvent in an amount sufficient to dissolve the components (A) and (B),

Sub B1